



The Electrochemical Society

First Call for Papers

**14th INTERNATIONAL SYMPOSIUM ON SEMICONDUCTOR
CLEANING SCIENCE AND TECHNOLOGY (SCST 14)**

**228th Electrochemical Society Meeting
Phoenix, Arizona, October 11 - 16, 2015**

This symposium has been organized under the auspices of the Electrochemical Society every other year since 1989. The symposium continues to cover a wide range of topics related to the science and technology of contaminants removal from as well as atomic layer etching and conditioning of Si(SOI), SiC, Ge, SiGe, III-V, II-VI semiconductor and non-semiconductor (e.g. sapphire, glass, ITO, plastic) surfaces; cleaning media, including non-aqueous cleaning methods and tools; FEOL and BEOL cleaning operations and pattern collapse prevention; integrated cleaning; cleaning of 3D structures and 3D stacked ICs, cleaning of MEMS; DUV and EUV masks; high-k and porous low-k dielectrics; post-CMP cleaning; wafer bevel cleaning/polishing; photoresist and residue removal, characterization, evaluation, and monitoring of cleaning; correlation with device performance; cleaning of equipment and storage/handling hardware; cleaning related issues specifically in the case of 450mm wafers and ultra-thin wafers; **as well as other issues within the broadly understood scope of this symposium.** Also, surface cleaning and conditioning topics involved in large-area electronics and photonics, both non-organic and organic TFT technology, compound semiconductor device processing, nanowire, nanotubes and nanodots cleaning, as well as surface conditioning related aspects of self-assembly-monolayer processing. Only original, non-commercial in nature contributions in any of the above listed topics will be accepted for presentation.

Depending on the number of accepted papers a poster session may be scheduled in addition to oral presentations. A hard-cover issue of *ECS Transactions* will be available at the meeting. Abstracts must be submitted electronically to ECS by **May 1, 2015**. Please check www.electrochem.org for abstract format and submission procedures. Following positive evaluation, authors will be requested to submit electronically, directly to ECS, a full-length camera-ready manuscript by **June 26, 2015**. Details regarding submission will be provided on the ECS website. All manuscripts will be submitted online, and must be in either MS Word or PDF format. Only papers submitted to the *ECS Transactions* and accepted for publication following a review process will be included in the program and scheduled for presentation during the symposium.

Additional information regarding this symposium can be obtained from the following co-organizers: **Jerzy Ruzyllo**, Penn State University, e-mail: jruzylo@psu.edu, **Takeshi Hattori**, Hattori Consulting International, e-mail: hattori@alumni.stanford.edu, **Paul Mertens**, IMEC vzw, e-mail: mertensp@imec.be, and **Richard E. Novak**, e-mail: richnovak@aol.com